

## AMENDMENTS TO THE CLAIMS

Claim 1 (Cancelled)

Claim 2 (Cancelled)

Claim 3 (Cancelled)

Claim 4 (Cancelled)

Claim 5 (Currently Amended) A dry etching method comprising etching a metallic surface of copper, silver, gold, or an alloy containing as a main component at least one of these metals by plasma of an etching gas containing a gaseous nitrogen oxide and ~~hydrogen, or nitrogen oxide and a hydrogen-containing compound~~ ammonia while being reacted with the plasma.

Claim 6 (Currently Amended) A dry etching method as claimed in Claim 5, wherein the ~~compound containing hydrogen is one or more members selected from the group consisting of ammonia, hydrocarbon, and~~ etching gas further contains hydrogen sulfide.

Claim 7 (Previously Presented) A dry etching method as claimed in Claim 5, wherein a mask material selected from the group consisting of titanium and a titanium alloy covers the metallic surface on etching.

Claim 8 (Previously Presented) A dry etching method as claimed in Claim 6, wherein a mask material selected from the group consisting of titanium and a titanium alloy covers the metallic surface on etching.